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Page 7, delete the whole paragraph starting in line 19 and replace it with the following new paragraph:

 $\rho_{\omega}$ 

- second object table (substrate table) WT proviced with a substrate holder for holding a substrate W (e.g. a resist-coated silicon wafer), and connected to second positioning means P1, P2 for accurately positioning the substrate with respect to item PL;

Page 7, delete the whole paragraph starting in line 34 and replace it with the following new paragraph:



The beam PB subsequently intercepts the mask MA which is held in a mask holder on a mask table MT. Having passed through the mask MA, the beam PB passes through the lens PL, which fouces the beam PB onto a target portion C of the substrate W. With the aid of the interferometric displacement measuring means IF, the substrate table WT can be moved accurately by the second positioning means PI, P2, e.g. so as to position different target portions C in the path of the beam PB. Similarly, the first positioning means M1, M2 and interferometric displacement measuring means can be used to accurately position the mask MA with respect to the path of the beam PB, e.g. after mechanical retrieval of the mask MA from a mask library. In general, movement of the object tables MT, WT will be realized with the air of a long stroke module (coarse positioning) and a short stroke module (fine positioning), which are not explicitlyly depicted in Figure 1.

Page 9, delete the whole paragraph starting in line 20 and replace with the following new paragraph:



Figure 3 is a partial cross-sectioned view of one position detection apparatus 10. As can there be seen the radiation source 11 and radiation detector 15 are mounted via bracket 16 to the metrology frame MF at such a position that the incident and return beams 12, 14 are inclined at an angle  $\delta$  to the X-Y plane, to which the wafer W is substantially parallel. Angle  $\delta$  is preferably substantially 45 degrees so that horizontal and vertical displacements of the reflector 13 relative to the incident light beam 12 of equal magnitude result in equal displacement of the return light beam 14 on the radiation detector 15.

Page 10, delete the whole paragraph starting in line 6 and replace with the following new paragrah: